L Number	Hits	Search Text	DB	Time stamp
-	139321	body near3 contact\$4	USPAT;	2004/09/20 1
			US-PGPUB; EPO; JPO; DERWENT;	
_	886566	gate	IBM_TDB USPAT; US-PGPUB;	2004/09/20 13
_	103991	parasiti\$6	EPO; JPO; DERWENT; IBM_TDB USPAT;	2004/09/20 1:
			US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	
-	476166	sti or isolating or isolation	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/09/20 1
-	44573	field adj3 (oxide or insulat\$5)	IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/09/20 1
-	369527	separat\$4 near4 (element or device or transistor)	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/09/20 1
_	836589	(sti or isolating or isolation) or (field adj3 (oxide or insulat\$5)) or (separat\$4	DERWENT; IBM_TDB USPAT; US-PGPUB;	2004/09/20 1
-	451	near4 (element or device or transistor))  (body near3 contact\$4) same gate same ((sti or isolating or isolation) or (field adj3 (oxide or insulat\$5)) or (separat\$4	EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/09/20 1
-	193	near4 (element or device or transistor)))	DERWENT; IBM_TDB USPAT; US-PGPUB;	2004/09/20 1
		<pre>adj3 (oxide or insulat\$5)) or (separat\$4 near4 (element or device or transistor)))) and parasiti\$6</pre>	EPO; JPO; DERWENT; IBM_TDB	
-	48279	(t or h) with gate	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/09/20 1
· -	40618	soi or (si or silicon) adj2 insulat\$4	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/09/21 1
-	836589	(sti or isolating or isolation) or (field adj3 (oxide or insulat\$5)) or (separat\$4 near4 (element or device or transistor))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/09/20 1
-	103991	parasiti\$6	IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/09/20 1
-	139321	body near3 contact\$4	DERWENT; IBM_TDB USPAT; US-PGPUB;	2004/09/20 1

_	116	silicon) adj2 insulat\$4) and ((sti or	USPAT; US-PGPUB;	2004/09/20 14:55
		isolating or isolation) or (field adj3 (oxide or insulat\$5)) or (separat\$4 near4	EPO; JPO; DERWENT;	
		(element or device or transistor)) ) and	IBM_TDB	
-	62047	parasiti\$6 and (body near3 contact\$4 ) bodytie or body adj2 tie or substrate adj3 (tie or contact)	USPAT; US-PGPUB;	2004/09/20 14:56
			EPO; JPO; DERWENT; IBM_TDB	
-	3793	<pre>(soi or (si or silicon) adj2 insulat\$4) and (bodytie or body adj2 tie or substrate adj3 (tie or contact))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/09/20 14:57
-	2400	<pre>((soi or (si or silicon) adj2 insulat\$4) and (bodytie or body adj2 tie or substrate adj3 (tie or contact))) and ((sti or isolating or isolation) or (field adj3 (oxide or insulat\$5)) or (separat\$4 near4 (element or device or transistor)))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 14:57
-	807		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 14:58
-	133	1 ±	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/20 14:59
_	1782		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/09/20 17:31
-	521029	parasitic\$4 or kink or float\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/09/20 17:31
-	626	(438/151.ccls. or 438/221.ccls. or 438/296.ccls.) and (parasitic\$4 or kink or float\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/09/20 17:32